

What is claimed is:

1. A substrate exposure system comprising:

a plurality of substrate transport means each of which sequentially transports one substrate to be a subject of

5 exposure to a measurement position and an exposure position;

one measuring head for measuring the substrate transported to the measurement position;

one exposure head for exposing the substrate transported to the exposure position;

10 measuring head-moving means for moving the measuring head to respective substrate-measuring positions for the respective substrates transported to the respective measurement positions of the plurality of substrate transport means; and

15 exposure head-moving means for moving the exposure head to respective substrate-exposing positions for the respective substrates transported to the respective exposure positions of the plurality of substrate transport means.

2. The substrate exposure system according to claim 1,  
20 wherein surfaces of the respective substrates transported to the respective exposure positions of the plurality of substrate transport means overlap in an exposing direction of the exposure head.

3. The substrate exposure system according to claim 1,  
25 further comprising: positional relationship-measuring means for measuring a relative positional relationship between the

substrate transported to the measurement position and the measuring head moved to the substrate-measuring position.

4. The substrate exposure system according to claim 2, further comprising: positional relationship-measuring means  
5 for measuring a relative positional relationship between the substrate transported to the measurement position and the measuring head moved to the substrate-measuring position.

5. The substrate exposure system according to claim 1, further comprising: exposure position-measuring means for  
10 measuring a relative positional relationship between the substrate transported to the exposure position and the exposure head moved to the substrate-exposing position.

6. The substrate exposure system according to claim 2, further comprising: exposure position-measuring means for  
15 measuring a relative positional relationship between the substrate transported to the exposure position and the exposure head moved to the substrate-exposing position.